

## Electronic supplementary information

# What are the Active Carbon Species during Graphene Chemical Vapor Deposition Growth?

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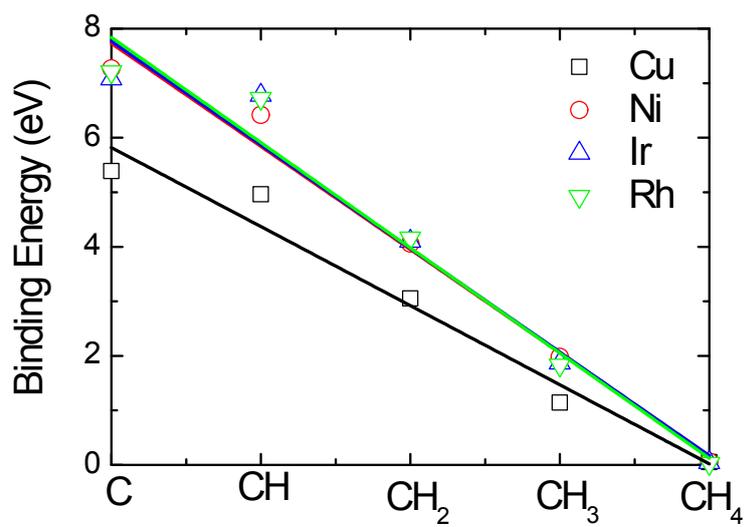
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**Table S1.** Comparison of binding energies  $E_b$  of various C precursors on Cu(111), Ni(111), Ir(111) and Rh(111) surfaces by using DFT-D2 and GGA-PBE methods. C-I and C-II represent the carbon monomer on metal surface and subsurface, respectively. The character T, F, and H denote the top, fcc, and hcp adsorption sites on metal surfaces, and O denotes the octahedral adsorption sites on metal subsurface, respectively. Here N/A represents that  $\text{CH}_4$  molecule is not sensitive to the adsorption sites of metal surfaces.

Metal Surface	$\text{CH}_i$ species	Stable adsorption site	$E_b$	
			DFT-D2	GGA-PBE
Cu(111)	C-I	F	3.39	4.90
	C-II	O	3.89	5.39
	CH	F	5.25	4.96
	$\text{CH}_2$	F	3.40	3.05
	$\text{CH}_3$	F	1.79	1.14
	$\text{CH}_4$	N/A	0.21	0.05
Ni(111)	C-I	H	5.29	6.76
	C-II	O	5.84	7.27
	CH	F	6.71	6.42
	$\text{CH}_2$	F	4.44	4.06
	$\text{CH}_3$	F	2.40	1.98
	$\text{CH}_4$	N/A	0.21	0.06
Ir(111)	C-I	H	5.68	7.08
	C-II	O	3.99	5.51
	CH	H (or F)	7.24	6.78
	$\text{CH}_2$	F	4.69	4.10
	$\text{CH}_3$	T	2.55	1.87
	$\text{CH}_4$	N/A	0.39	0.04
Rh(111)	C-I	H	5.71	7.21
	C-II	O	5.45	6.90
	CH	H	7.04	6.72
	$\text{CH}_2$	F	4.09	4.16
	$\text{CH}_3$	F	2.27	1.83
	$\text{CH}_4$	N/A	0.25	0.03



**Fig. S1** The binding energies of  $\text{CH}_i$  ( $i = 0, 1, 2, 3, 4$ ) species on Cu, Ni, Ir, and Rh surfaces as a function of the number of H in the  $\text{CH}_i$  species.

### Computational details for relative Gibbs free energy

The relative Gibbs free energy ( $\Delta G_f$ ) of  $\text{CH}_i$  species ( $i = 0, 1, 2,$  and  $3$ ) on metal surfaces is defined as,<sup>1-3</sup>

$$\Delta G_f = E_T - E_M + \Delta F_{\text{vib}} - n_C \mu_C - n_H \mu_H \quad (1)$$

where  $E_T$  and  $E_M$  are total energies of metal surface with and without adsorbed  $\text{CH}_i$ , respectively,  $n_C = 1$  and  $n_H = i$  are the number of C and H atoms in  $\text{CH}_i$ , respectively.

$\Delta F_{\text{vib}}$  is the change of vibrational contributions of  $\text{CH}_i$  species on metal surfaces to system free energy.  $F_{\text{vib}}$  is defined as<sup>3</sup>

$$F_{\text{vib}}(\omega, T) = \hbar\omega \left( \frac{1}{2} + \frac{1}{e^{\beta\hbar\omega} - 1} \right) - kT \left[ \frac{\beta\hbar\omega}{e^{\beta\hbar\omega} - 1} - \ln(1 - e^{-\beta\hbar\omega}) \right] \quad (2)$$

where  $\beta = 1/kT$  and  $\omega$  is the vibrational frequency of  $\text{CH}_i$  species on metal surfaces.

$F_{\text{vib}}$  is equal to the zero-point energy (ZPE) at the temperature  $T = 0$  K. Table S2 lists zero-point energies (ZPE), vibrational entropies multiplied by temperature ( $T = 1200$  K), and total vibrational contributions to the free energy of various  $\text{CH}_i$  species ( $i=0, 1, 2,$  and  $3$ ) on Cu(111), Ni(111), Ir(111) and Rh(111) surfaces.  $\mu_H$  is the hydrogen chemical potential, that is a function of temperature and  $\text{H}_2$  partial pressure. The  $\mu_H$  can be written as,<sup>1,2</sup>

$$2\mu_H(T, p) = E_{\text{H}_2} - kT \ln \left( \frac{kT}{p} \times g \times \zeta_{\text{trans}} \times \zeta_{\text{rot}} \times \zeta_{\text{vib}} \right) \quad (3)$$

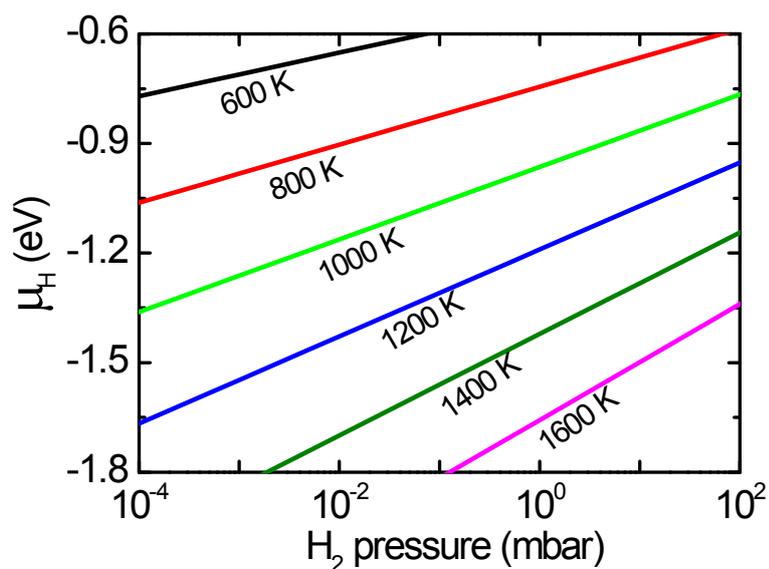
where  $E_{\text{H}_2}$  is DFT calculated energy of a hydrogen molecule (-6.760 eV),  $k$  is Boltzmann constant,  $p$  is partial pressure of  $\text{H}_2$ , and  $g$  is the degree of degeneracy of the electron energy level.  $\zeta_{\text{trans}}$ ,  $\zeta_{\text{rot}}$ , and  $\zeta_{\text{vib}}$  are the partition functions for translational, rotational, and vibration motions, respectively. Taking one-half of the energy of a  $\text{H}_2$  molecule ( $E_{\text{H}_2}$ ) as a reference, the dependence of  $\mu_H$  on temperature  $T$  and  $\text{H}_2$  partial pressure  $p$  is shown in Fig. S2.  $\mu_C$  is carbon chemical potential and it depends on growth temperature  $T$  and the partial pressure ratio of  $\text{CH}_4$  and  $\text{H}_2$  during the growth,<sup>4</sup>

$$\mu_C(T, \frac{P_{\text{CH}_4}}{P_{\text{H}_2}}) = \Delta E - 2\mu_H^* + kT \ln \frac{P_{\text{CH}_4}}{P_{\text{H}_2}} \quad (4)$$

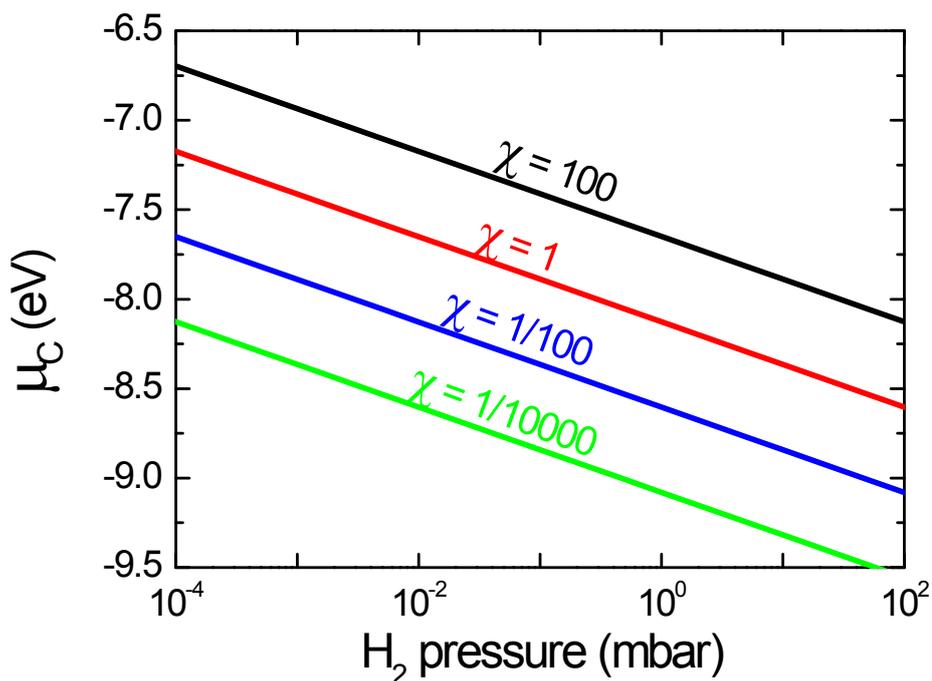
where  $\Delta E$  is the DFT energy difference of  $\text{CH}_4$  and  $\text{H}_2$  molecules ( $\Delta E = E_{\text{CH}_4} - 2E_{\text{H}_2} = -10.507$  eV), and  $\mu_H^*$  is related to the term of  $T$  and  $\text{H}_2$  pressure of Eq.(3).

**Table S2.** Zero-point energies (ZPE), vibrational entropies multiplied by temperature ( $T = 1200$  K), and vibrational contributions to the free energy of various  $\text{CH}_i$  species ( $i=0, 1, 2,$  and  $3$ ) on Cu(111), Ni(111), Ir(111) and Rh(111) surfaces. C-I and C-II represent the carbon monomer on metal surface and subsurface, respectively.

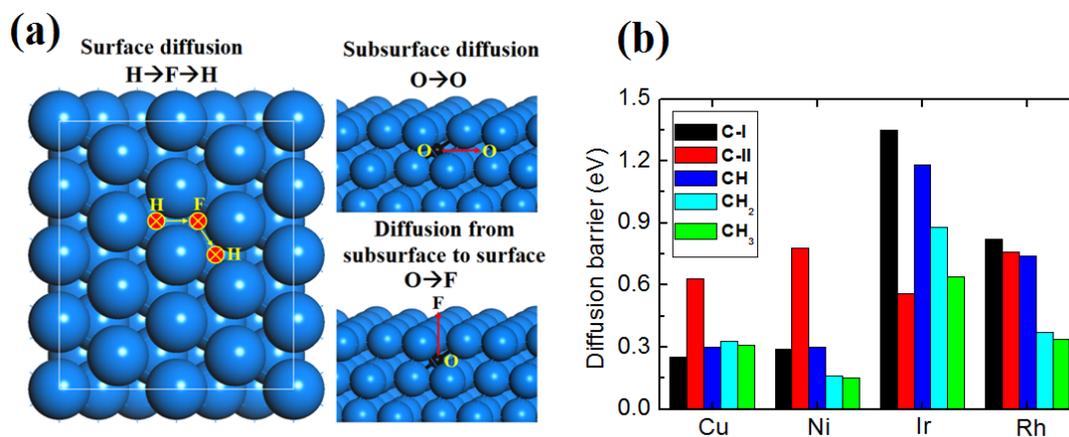
Surface	$\text{CH}_i$	ZPE (eV)	TS (eV)	$F_{\text{vib}}$ (eV)
Cu(111)	C-I	0.09	0.30	-0.21
	C-II	0.10	0.30	-0.20
	CH	0.34	0.52	-0.18
	$\text{CH}_2$	0.58	0.78	-0.20
	$\text{CH}_3$	0.91	0.95	-0.04
Ni(111)	C-I	0.11	0.29	-0.18
	C-II	0.11	0.29	-0.18
	CH	0.35	0.51	-0.16
	$\text{CH}_2$	0.57	0.78	-0.21
	$\text{CH}_3$	0.89	0.94	-0.05
Ir(111)	C-I	0.10	0.30	-0.20
	C-II	0.10	0.30	-0.20
	CH	0.38	0.50	-0.12
	$\text{CH}_2$	0.59	0.74	-0.15
	$\text{CH}_3$	0.95	1.11	-0.16
Rh(111)	C-I	0.10	0.30	-0.20
	C-II	0.10	0.30	-0.20
	CH	0.36	0.51	-0.15
	$\text{CH}_2$	0.59	0.74	-0.15
	$\text{CH}_3$	0.88	0.95	-0.07



**Fig. S2** The dependence of H chemical potential  $\mu_{\text{H}}$  (eV) on temperature  $T$  and  $\text{H}_2$  pressure  $p$ . Here one-half of the energy of a  $\text{H}_2$  molecule is taken as a reference.



**Fig. S3** The carbon chemical potential  $\mu_C$  (eV) as a function of  $H_2$  pressure ( $P_{H_2}$ ) for the ratio of partial pressures between  $CH_4$  and  $H_2$  ( $\chi = P_{CH_4} / P_{H_2}$ ) at 100, 1, 1/100, and 1/10000.



**Fig. S4** (a) Diffusion pathways and (b) diffusion barriers of various  $CH_i$  species ( $i = 0, 1, 2, 3$ ) on Cu(111), Ni(111), Ir(111), and Rh(111) surfaces. The surface diffusion pathway is  $H \rightarrow F \rightarrow H$ , the diffusion pathway of C atom in metal subsurface is  $O \rightarrow O$ , and the diffusion pathway of C atom from subsurface to surface is  $O \rightarrow F$ . C-I and C-II represent the carbon atom on metal surface and subsurface, respectively.

## Notes and references

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